

DEVICE FOR TREATING AN OBJECT WITH PLASMA

ABSTRACT

5 The invention concerns a system (1) for the plasma
processing of an object (3) comprising a processing
vacuum chamber (10) comprising a support on which the
object to be treated is placed, at least two
subassemblies (21, 22) each comprising at least one
10 plasma source (210, 220) suitable for generating a
plasma and being supplied independently by
radiofrequency power P_i and by a gas i at a flow rate
 n_i . According to the invention, the plasma generated by
one of the subassemblies (21) is a partially ionized
15 gas or a gas mixture, of different chemical nature from
the plasma generated by the other subassembly or
subassemblies (22).

 The present invention also concerns a selective
processing process of a composite object implementing
20 such a device.

FIGURE 3